Application of: Euijoon Yoon et al.

Serial No.: 10/596,126

Amendment after Non-Final Office Action

AMENDMENTS TO THE ABSTRACT

Please replace the Abstract with the following paragraph:

[Abstract]

The present invention relates to a growth method of nitride semiconductor layer eomprising a first step for growing Growing a first nitride 5 semiconductor layer on an $\underline{Al_xGa_yIn_{1-x-y}N(0\leq x\leq 1,\ 0\leq y\leq 1,\ 0\leq x+y\leq 1)}\ \underline{Al_xGa_yIn_{1-x-y}N(0\leq x\leq 1,\ 0\leq y\leq 1,\ 0\leq x+y\leq 1)}\ layer,\ a$ second step for reducing the thickness of the first nitride semiconductor layer by growth interruption and, a third step for growing a second nitride semiconductor layer having a band gap energy higher than that of the first nitride semiconductor layer on the first nitride semiconductor

layer with the [[to]] reduced thickness and a light emitting device using the growth method.